L Number		Search Text	DB	Time stamp
_	165605	consist\$3 same (nh3 nh?sub.3 ammonia n2	USPAT	2004/06/24 19:15
		n?sub.2 nitrogen h?sub.2 h2 hydrogen		
		methan ch4 ch?sub.4)		
-	97570	(consist\$3 same (nh3 nh?sub.3 ammonia n2	USPAT	2004/06/24 19:21
		n?sub.2 nitrogen h?sub.2 h2 hydrogen		
		methan ch4 ch?sub.4)) and consist\$3 near10		
		(nh3 nh?sub.3 ammonia n2 n?sub.2 nitrogen		
		h?sub.2 h2 hydrogen methan ch4 ch?sub.4)		
-	13832	((consist\$3 same (nh3 nh?sub.3 ammonia n2	USPAT	2004/06/24 19:17
		n?sub.2 nitrogen h?sub.2 h2 hydrogen		
		methan ch4 ch?sub.4)) and consist\$3 near10		
		(nh3 nh?sub.3 ammonia n2 n?sub.2 nitrogen		
		h?sub.2 h2 hydrogen methan ch4 ch?sub.4))		
		and (photoresist resist residu\$2) near15		
		(nh3 nh?sub.3 ammonia n2 n?sub.2 nitrogen		
		h?sub.2 h2 hydrogen methan ch4 ch?sub.4)		
	1027	(((consist\$3 same (nh3 nh?sub.3 ammonia n2	USPAT	2004/06/24 19:18
		n?sub.2 nitrogen h?sub.2 h2 hydrogen		
		methan ch4 ch?sub.4)) and consist\$3 near10		
		(nh3 nh?sub.3 ammonia n2 n?sub.2 nitrogen		
		h?sub.2 h2 hydrogen methan ch4 ch?sub.4))		
		and (photoresist resist residu\$2) near15		
		(nh3 nh?sub.3 ammonia n2 n?sub.2 nitrogen		
		h?sub.2 h2 hydrogen methan ch4 ch?sub.4))		
		and (257/\$.ccls. 438/\$.ccls. 427/\$.ccls.		
		156/\$.ccls.)		
-	405	((((consist\$3 same (nh3 nh?sub.3 ammonia	USPAT	2004/06/24 19:20
		n2 n?sub.2 nitrogen h?sub.2 h2 hydrogen		
}		methan ch4 ch?sub.4)) and consist\$3 near10		
		(nh3 nh?sub.3 ammonia n2 n?sub.2 nitrogen		
		h?sub.2 h2 hydrogen methan ch4 ch?sub.4))		
		and (photoresist resist residu\$2) near15		
		(nh3 nh?sub.3 ammonia n2 n?sub.2 nitrogen		
		h?sub.2 h2 hydrogen methan ch4 ch?sub.4))		
		and (257/\$.ccls. 438/\$.ccls. 427/\$.ccls.		
		156/\$.ccls.)) and (hole\$1 opening\$1	•	
		trench\$2 groove\$1 aperture\$1 recess\$3		
		cavit\$3 via\$1) same (resit polymer\$2		
		photoresist residu\$2)		
-	310	(((((consist\$3 same (nh3 nh?sub.3 ammonia	USPAT	2004/06/24 19:21
		n2 n?sub.2 nitrogen h?sub.2 h2 hydrogen		
		methan ch4 ch?sub.4)) and consist\$3 near10		
		(nh3 nh?sub.3 ammonia n2 n?sub.2 nitrogen		
		h?sub.2 h2 hydrogen methan ch4 ch?sub.4))		
		and (photoresist resist residu\$2) near15		
		(nh3 nh?sub.3 ammonia n2 n?sub.2 nitrogen		
		h?sub.2 h2 hydrogen methan ch4 ch?sub.4))		
		and (257/\$.ccls. 438/\$.ccls. 427/\$.ccls.		
		156/\$.ccls.)) and (hole\$1 opening\$1		
		trench\$2 groove\$1 aperture\$1 recess\$3		
		cavit\$3 via\$1) same (resit polymer\$2		
		photoresist residu\$2)) and (hole\$1		
		opening\$1 trench\$2 groove\$1 aperture\$1		
		recess\$3 cavit\$3 via\$1) near10 (clean\$3		
		etch\$3 remov\$3)	l	

	210	1/////	TIODAM	2004/06/24 10-22
-	310	(((((consist\$3 same (nh3 nh?sub.3 ammonia	USPAT	2004/06/24 19:22
		n2 n?sub.2 nitrogen h?sub.2 h2 hydrogen		1
		methan ch4 ch?sub.4)) and consist\$3 near10		
	1	(nh3 nh?sub.3 ammonia n2 n?sub.2 nitrogen		
		h?sub.2 h2 hydrogen methan ch4 ch?sub.4))		
		and (photoresist resist residu\$2) near15		
		(nh3 nh?sub.3 ammonia n2 n?sub.2 nitrogen		
		h?sub.2 h2 hydrogen methan ch4 ch?sub.4))		
		and (257/\$.ccls. 438/\$.ccls. 427/\$.ccls.		
		156/\$.ccls.)) and (hole\$1 opening\$1		
		trench\$2 groove\$1 aperture\$1 recess\$3		
		cavit\$3 via\$1) same (resit polymer\$2		
		photoresist residu\$2)) and (hole\$1		
		opening\$1 trench\$2 groove\$1 aperture\$1		
		recess\$3 cavit\$3 via\$1) near10 (clean\$3		
		etch\$3 remov\$3)) and consist\$3 near10 (nh3		
		nh?sub.3 ammonia n2 n?sub.2 nitrogen		
		h?sub.2 h2 hydrogen methan ch4 ch?sub.4)		